

AUG 0 3 2007

PATENT

Atty. Docket No.: 006915 USA P02/FEP/P3I/AG RW Ref. No.: APM/001-02-CP1-2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Kenneth Collins, et al.

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Entitled: PLASMA IMMERSION ION

IMPLANTATION APPARATUS USING A

PLASMA SOURCE HAVING LOW

DISSOCIATION AND LOW MINIMUM

PLASMA VOLTAGE

: Group Art Unit: 2813

: Examiner: Jack S. Chen

Serial No.: 10/646,533

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Filing Date: August 22, 2003

RESPONSE TO DOUBLE PATENTING REJECTION

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In response to the Office Action (Double Patenting) dated July 11, 2007, applicants submit herewith a Terminal Disclaimer to overcome the double patenting rejection.

Although the claims have not been amended, a complete listing of claims is provided and begins on page 2.

Remarks begin on page 17 of this paper.